

(Use several sheets if necessary)

SERIAL NO.  
PCT/JP00/06038

09/830598

JC18  
September 6, 2000

JC18 Rec'd CRUPTO 27 APR 2001

1756

[illegible]

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
		10-78647	03-1998	JAPAN				✓
		7-219204	08-1995	JAPAN				✓
		7-168343	07-1995	JAPAN				✓
		6-282063	10-1994	JAPAN				✓
		5-175346	06-1994	JAPAN				✓


DATE CONSIDERED

4/25/03

P09C/REV03

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**INFORMATION DISCLOSURE STATEMENT**  
(Use several sheets if necessary)

Docket Number (Optional)

A-398

Application Number

09/830,598 (PCT/JP00/06038)

Applicant(s)

Junji FUJIKAWA et al

Filing Date

April 27, 2001 (Feb. 5, 2003)

Group Art Unit

1756

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JS		5,482,799	01-1996	Isao et al	430	5	
JS		5,721,075	02-1998	Hashimoto et al	430		

**FOREIGN PATENT DOCUMENTS**

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

SMITH B W ET AL: "ATTENUATED PHASE SHIFT MASK MATERIALS FOR 248- AND 193-NM LITHOGRAPHY"  
MICROLITHOGRAPHY WORLD, PENNWEILL PUBLISHING COMPAGNY, US, vol. 6, no. 2, 21 March 1997  
(1997-03-21), pages 7-8, 10, 12, 19, XP000688905 ISSN: 1074-0407

EXAMINER

*J. D. [Signature]*

DATE CONSIDERED

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.